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Development of Complex Curricula for Molecular Bionics and Infobionics Programs within a consortial* framework**

Consortium leader

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Consortium members

SEMMELWEIS UNIVERSITY, DIALOG CAMPUS PUBLISHER

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**Molekuláris bionika és Infobionika Szakok tananyagának komplex fejlesztése konzorciumi keretben

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VLSI Design Methodologies

(VLSI tervezési módszerek)

Image sensors and their design

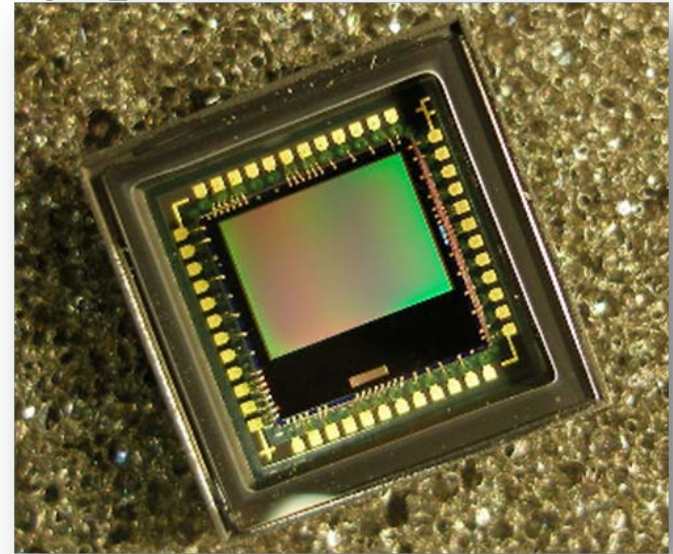
(Képszenzorok és tervezésük)

PÉTER FÖLDESZ

The topics are covered in this chapter:

- Architecture
- Optical characteristics and materials
- Noise and the dynamic range issues
- CCD v. CMOS sensors
- Architectures
- Conclusions

- Architecture of photosensors
 - Optical focusing
 - Color filtering (usually IR and UV)
 - Photon to charge converter (e.g. photodiode)
 - Array addressing
 - Amplifier and correlated double sampling for noise reduction
 - Converter
 - Digital post processing



Section I

Optical characteristics and materials, physics of light sensing

Optical Characteristics

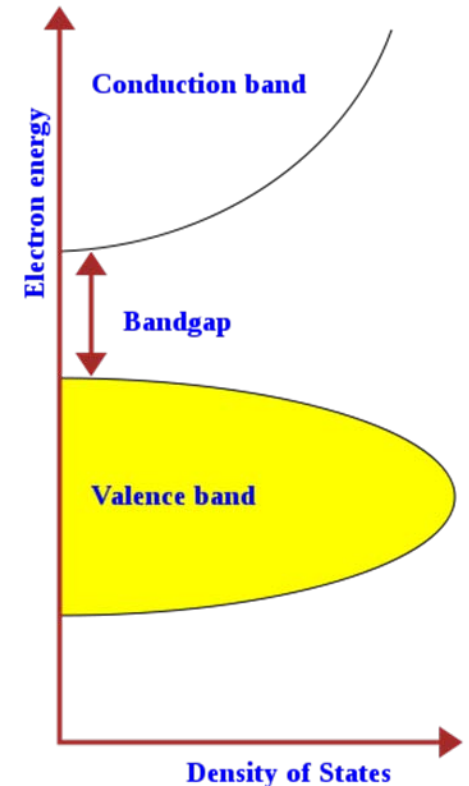
- Absorption of Photons
- Light Sensitivity
- Quantum Efficiency
- Fill Factor, Micro-Lenses
- Dynamic range
- Others
 - Smear, Blooming
 - Electronic Shuttering
 - Sampling, Aliasing, MTF

Absorption of Photons

- Convert optical energy into electrical energy
- Energy-band structure
 - Conduction and valence band
- Direct or indirect bandgap materials
 - Si – indirect
 - GaAs, GaAlAs, InP – direct
 - Nanoscale plasmon enhanced combinations
- The difference is whether phonon generation required in electron state transition or not

Absorption of Photons

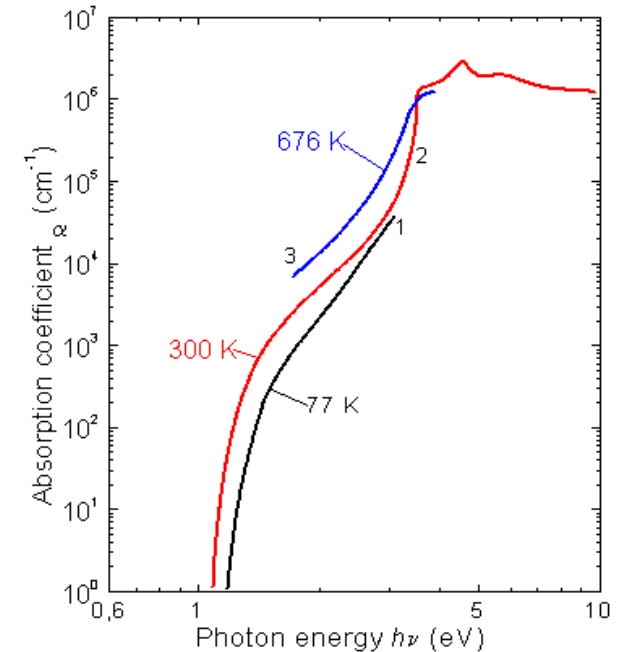
- In order for an electron to jump from a valence band to a conduction band, it requires specific minimum amount of energy.
- The required energy alters with different materials.
- Electrons can gain energy to flip to the conduction band by absorbing either a phonon (heat) or a photon (light).



http://en.wikipedia.org/wiki/File:Bandgap_in_semiconductor.svg

Absorption of Photons

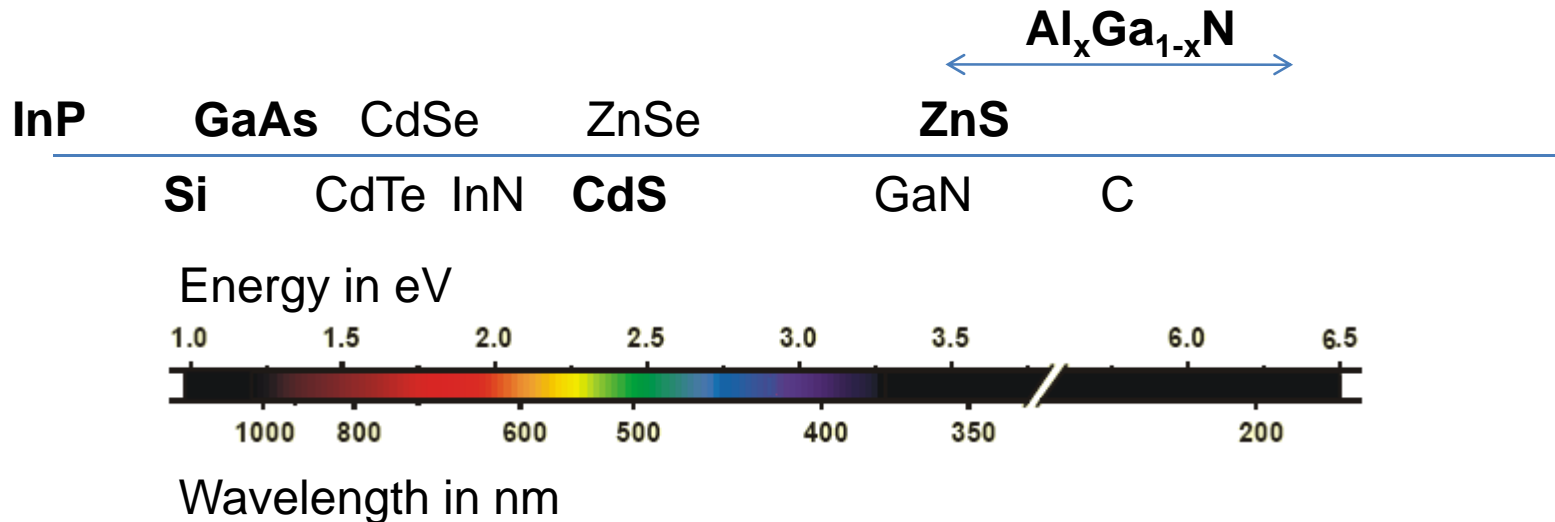
- Energy of the photon ($E = hc/\lambda$) $> E_g$, electron-hole pair may be generated
- Visible range: 1.7-3.1 eV
- Penetration depth
 $\sim \exp(-\alpha * \text{depth})$
- Note the strong temperature dependence



Silicon absorption curve

<http://www.ioffe.rssi.ru/SVA/NSM/Semicond/Si/Figs/145.gif>

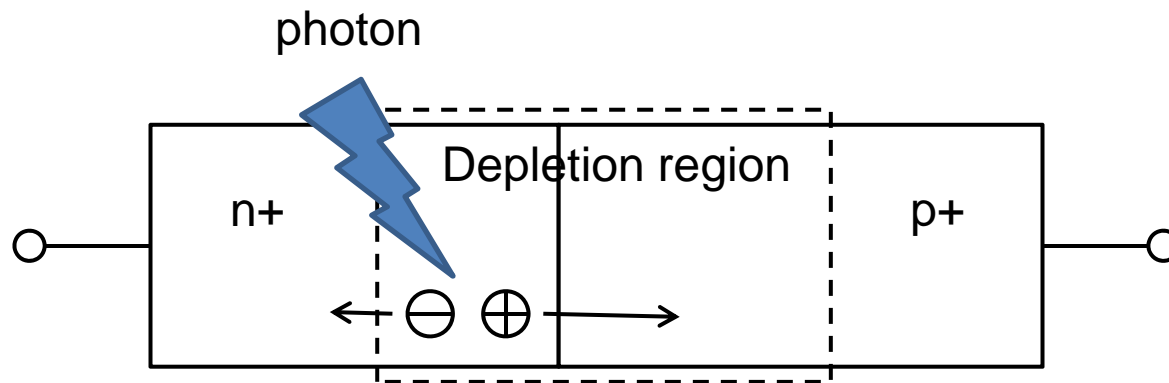
- *Band gaps* of different materials



Separation of electron hole pairs

- Electron-hole pair generation by photons
 - But, electron-hole pair recombination always work
- With a large electric field we can separate the pairs, making the detection.
 - The most simplest form is the photodiode.
- More advanced and better is to collect electrons in potential traps
 - This way works the so called pin photodiodes
 - The CCD image sensors.

- Depletion region with large electric field
 - Quick drift, no recombination.
- Quasineutral region, with no electric field
 - Loss, but drift length is μm range, may be detected in a nearby depletion region
- Higher doping level \rightarrow smaller drift length



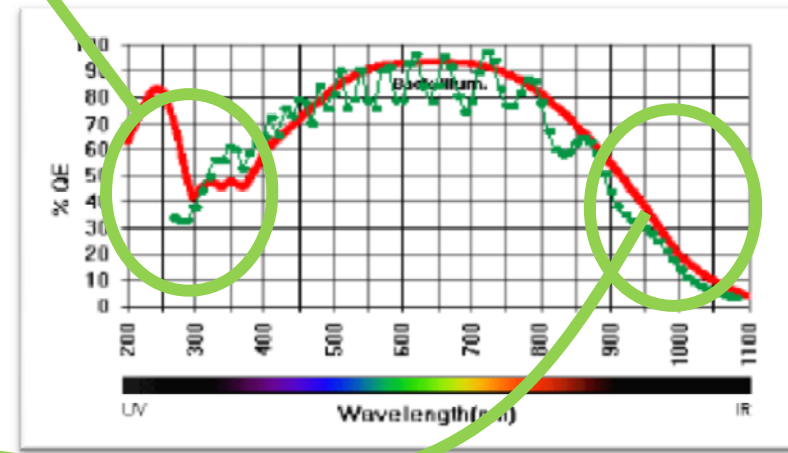
Section II

Light sensing efficiency, measures, and ways to increase

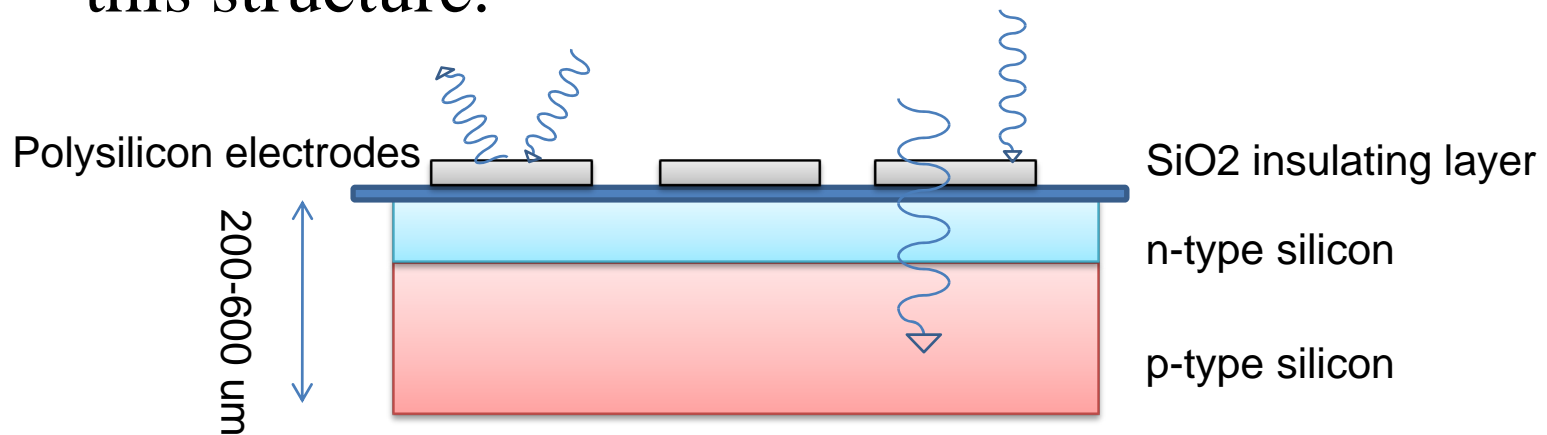
Efficiency measures

- The efficiency can be measured in different ways, depending on what kind of loss we are expressing.
- *Optical efficiency*
 - Defined as $1-R$, where R is the reflectivity of the system
- *Quantum efficiency*
 - Describes the efficiency of the photon absorption that becomes useful signal.
 - External: number of the detected electron-hole pairs divided by the incident photons
 - Internal: same as external, but counts the penetrated photons only

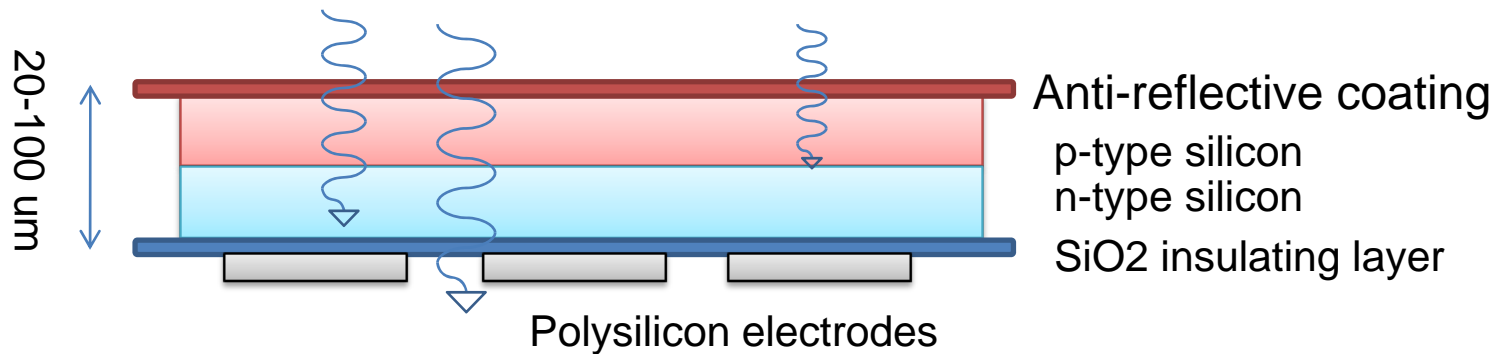
- Efficiency depending on the wavelength.
- High energy photons
 - Shallow penetration depth
 - Highly doped N+ (not depletion region) low drift length, no detection
- Low energy photons
 - Deeper penetration depth
 - Out of the depletion region, drift long, but diffuse
 - Finally does not detected



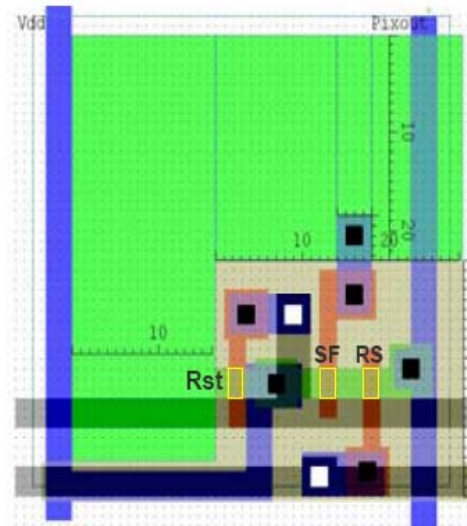
- Solution for increasing sensitivity of detection of the lower energy photons: *Front side illumination* (poor blue response). Most of the cameras follow this structure.



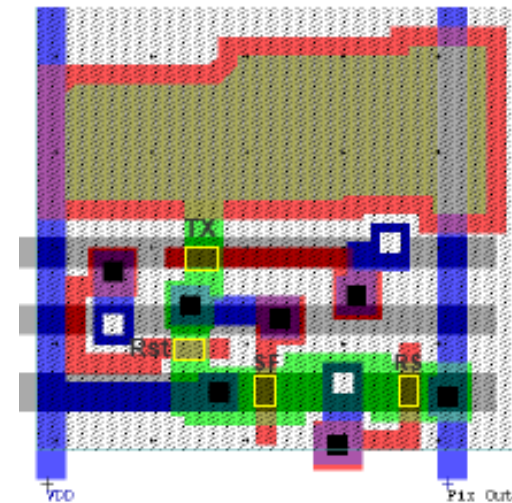
- Solution for increasing sensitivity of detection of the higher energy photons: *Back illumination* (poor red response, astronomical CCDs)



- Internal quantum efficiency
 - *Fill factor*. The photosensitive area divided by the pitch of the sensor array. Note that below the larger portions are the sensitive area, the rest is the readout electronics.

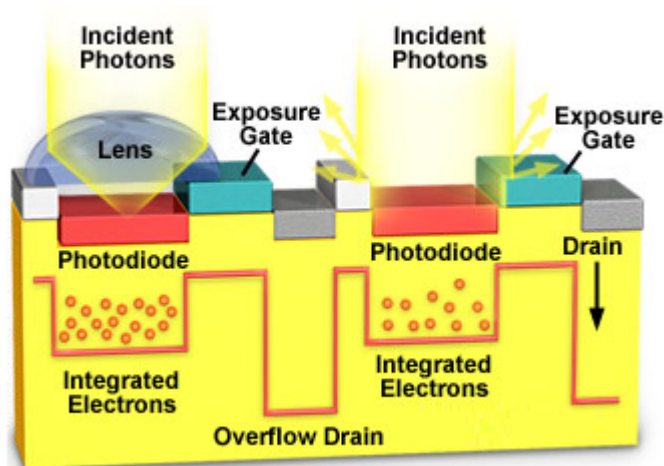


Photodiode

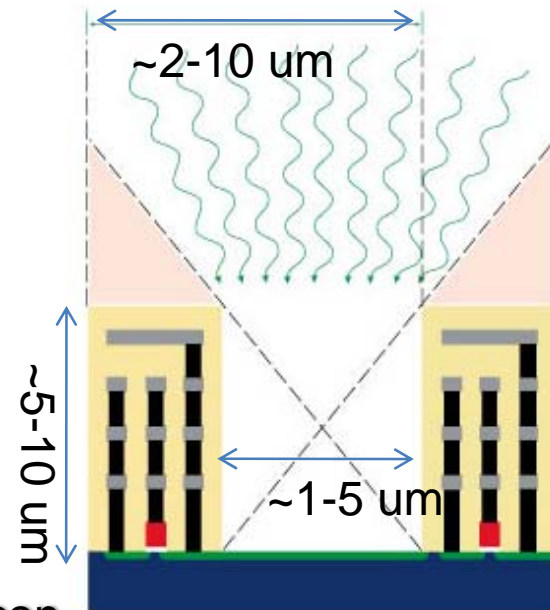


Photogate

- Fill factor can be increased by microlenses (or lenslet). The blooming is also reduced
 - Nowadays a standard method in cameras
- The walls of metalization also degrade quality and view angle



Active silicon



- Color detection

- Filter Wheel
- Prism

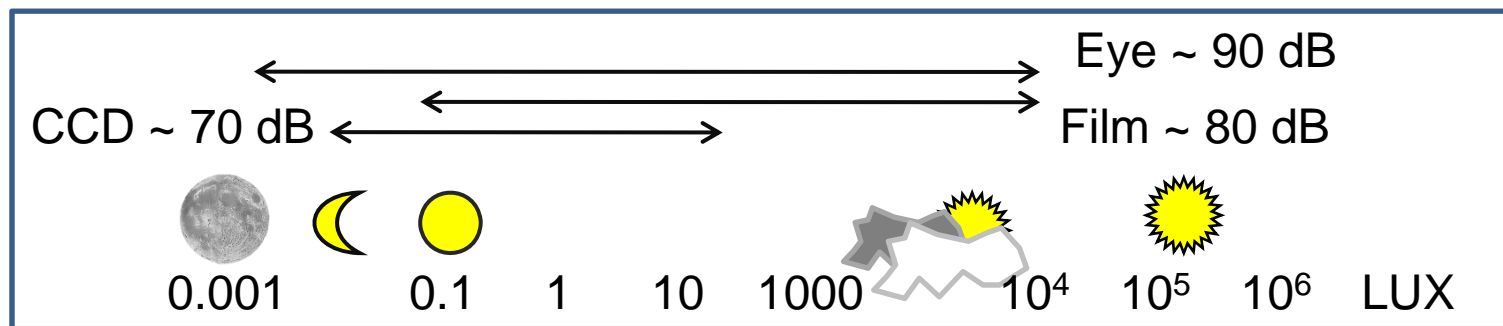


- Color Filters

- Mosaic (e.g Bayer) and in stripe configuration
- in primary (RGB) and in complementary colors (CMY)
- matrixing and color de-mosaicing (aliasing: nearest neighbor, linear, cubic, and cubic spline)
- Different wavelength propagates different depth (see Foveon technologies)

Dynamic range

- Classic integration type diode sensor: restricted by the full well capacity (max electrons in the charge collection area)
- Noise floor (measured in electrons)
- Voltage range allowed on the capacitor (diode)



- Dynamic range:
 - Eye 90 dB, film 80 dB, CMOS/CCD 65-75 dB
- Methods to increase:
 - Compressing sensors, such as logarithmic compressed-response photodetectors;
 - Multi-mode sensors, where operation modes are changed;
 - Frequency-based sensors, where the sensor output is converted to pulse frequency;

- Methods to increase:
 - Sensors with external control over integration time
 - global control (where the integration time of the whole sensor can be controlled)
 - local control (where different areas within the sensor can have different exposure times);
 - Sensors with autonomous control over integration time

- Noise and The Dynamic Range
 - Reset of Noise
 - Incomplete reset the integration level (blur from previous value)
 - Thermal noise, the moment of switch off the reset switch
 - Shot Noise
 - Statistical fluctuations in the amount of illumination
 - The smaller the sensor, larger the noise
(10 Mpixel = 2-3 μm sensor \sim 10,000 e- capacity)

- Noise and The Dynamic Range
 - $1/f$ of the electronics
 - Quantization of Noise
 - ADC resolution, 10-12 bit
 - Fixed Pattern Noise
 - Solution: correlated double sampling (CDS)
 - Dark current; readout noise
 - CCD – 1-10 e⁻ (even electron per hour level!)
 - CMOS – 1-15 fAmp; 20-200 e⁻

Section III

CMOS versus CCD technologies

CCD versus CMOS sensors

	CCD Approach	CMOS Approach
Pixel	<p>Photodiode</p> <p>Charge generation and charge integration</p>	<p>Photodiode + Amplifier</p> <p>Charge generation, charge integration and charge-to-voltage conversion</p>
Array Readout	<p>Charge transfer from pixel to pixel</p>	<p>Multiplexing of pixel voltages: Successively connect amplifiers to common bus</p>
Sensor Output	<p>Output amplifier performs charge-to-voltage conversion</p>	<p>Various options possible:</p> <ul style="list-style-type: none"> - no further circuitry (analog out) - add. amplifiers (analog output) - A/D conversion (digital output)

CCD versus CMOS sensors

CCD

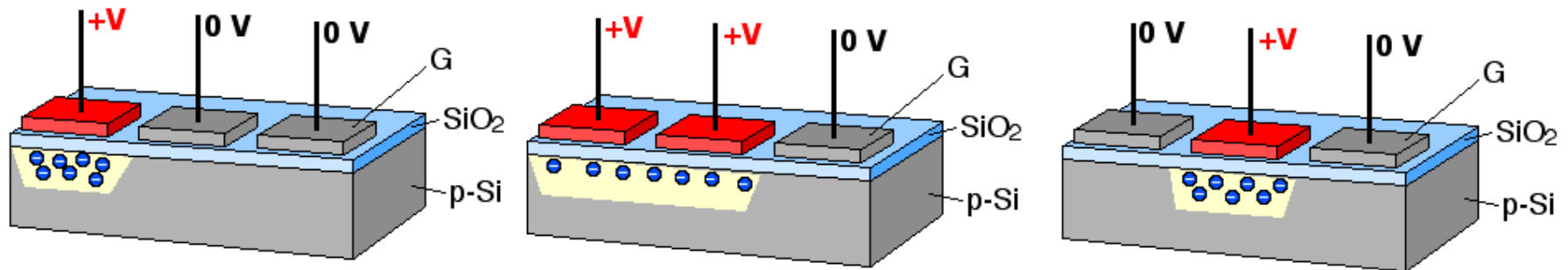
- Expensive in small number (mass product)
- Sensitive, has low noise, hence better dynamic range
- Serial readout
- Special sensors for moving scenes and extremely low light conditions

CCD versus CMOS sensors

CMOS

- Cheap – mass production for cameras, cell phones, web cameras
- Noisy, as the photons are converted to potential and handled as voltage.
- Random access available.
- Integrated camera components (e.g. camera on chip with MPEG coding)

- Architecture and variants for CCD
 - Charge coupled devices. Based on charge transfer mechanism (shift register) driven by three phase potential change and separated wells for electrons.



History: first as shift register has been used, but after they identified its light sensitivity, Sony started mass production of CCDs with light sensitivity for camcorders.

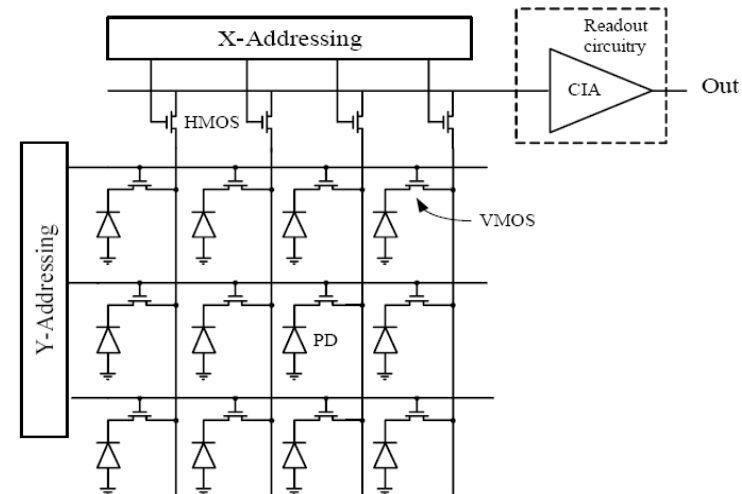
- Architecture and variants for CCD
 - In electron-multiplying CCD (L3Vision CCD) a gain register is placed at the output.
 - The gain register is split up into a number of stages. In a stage the electrons are multiplied by impact ionization (gain > 500). Used in astronomy, its noise is as low as of 0.01 to 1 e-.
 - Time-delay-and-integration CCD (TDI-CCD) for fast objects. The image is transferred and captured again.

- CMOS architectures for pixels and converters
 - *Passive pixel sensor*
 - *Active pixel sensor*
 - Photodiodes
 - Photogates
 - Pinned photodiode
 - Specials
 - Phototransistor
 - Logarithmic
 - Snapshot
 - ADC position relative to the pixel array

Section IV

CMOS sensor architectures

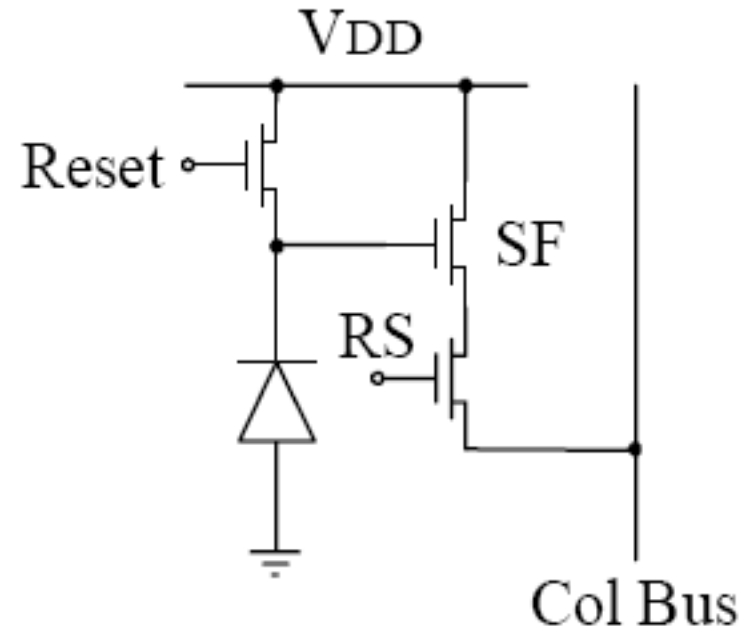
- Passive pixel architecture
 - The PPS consists of a photodiode and just one transistor
 - The passive pixel structure has major problems due to its large capacitive loads
 - Readout noise large (250 e⁻)
 - Fill factor near 100%



- Active pixel architecture
 - Fill factor 50-70%
 - Lower readout noise (20-100 e-)
 - Faster than PPS and well scalable
 - Types:
 - Photodiodes, Photogates, Pinned
 - Correlated double sampling (CDS) can suppress reset noise, 1/f noise and FPN due to threshold voltage and lithographic variations in the array.

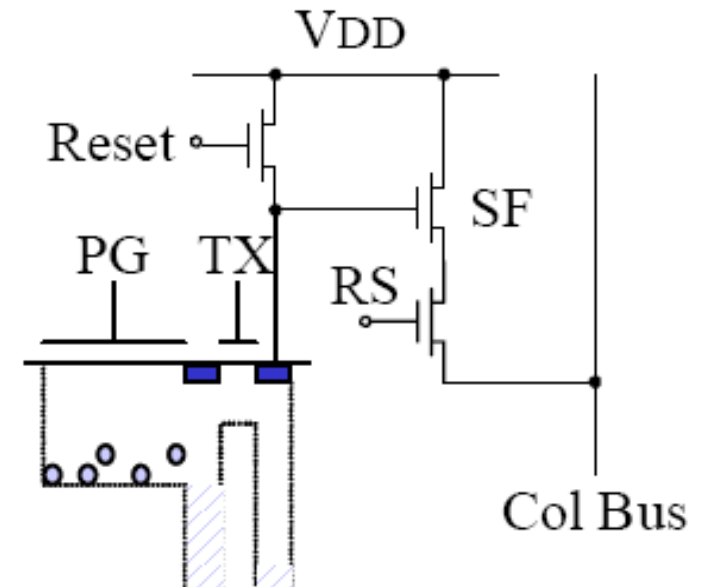
• Photodiodes

- photodiode and a readout circuit of three transistors: a photodiode reset transistor (Reset), a row select transistor (RS) and a source-follower transistor (SF).
- Its structure is the most frequent



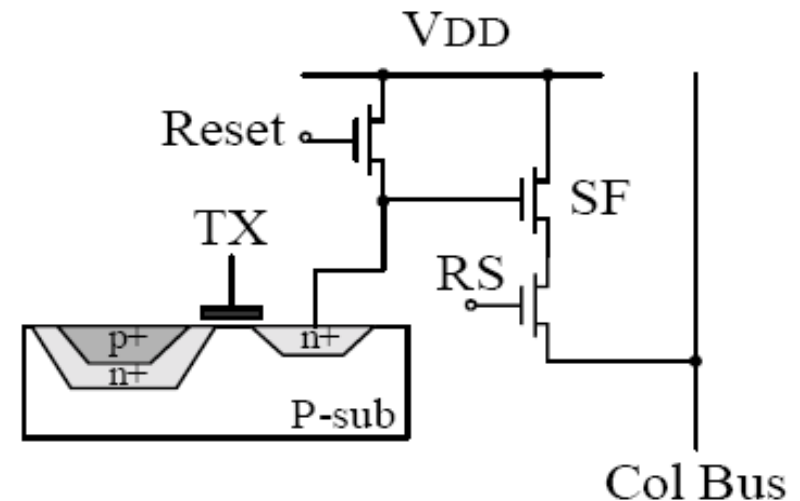
• Photogate

- basic concept for the photogate pixel arose from CCD technology
- photon-generated charge is integrated under a photogate with a high potential well
- Reduced fill factor, QE
- Bad blue response



- Pinned photodiodes

- Similar to photogate, but p+ generates the depletion region
- Pinned diode (p+-n-p)
- Small photon collection area (less e-)
- Many sensor uses it
- Very tricky layout



- Electronic shutter
 - Non rolling mode, but synchronous operation
 - The pixel includes a sample-and-hold (S/H) switch with analog storage
- Special sensors
 - Logarithmic, Lateral Bipolar Phototransistor
 - Enables logarithmic encoding (LOG) of the photocurrent, thus increasing the dynamic range
 - Significant temperature dependence of the output, low swing of the output, current gain non-uniformity

ADC position

- Off chip:
 - typically CCD
- On chip
 - One fast ADC
 - Typical CMOS sensors (10-50 fps)
 - One per column
 - Fast cameras (up to 1000 fps)
 - One per pixel
 - Pixim HDR sensor (not speed but multisnapshot solution)

Example of a real camera chip:

- Sony ICX285AL Exview HAD
- CCD, Pixel size: 6.45 μ M x 6.45 μ M
- Image area: 8.98mm (Horizontal) x 6.7mm (Vertical)
- Spectral Response: QE max at 540nm (~65%), 50% roll-off at 400nm and 750nm.
- Readout Noise: Less than 12 e- RMS.
- Full-well capacity: Greater than 27,000 e-
- Less than 0.02 electrons/second @ + 10C ambient!
- Data format: 16 bits
- Critics: 27,000 e- / 12 e- => 2250 levels clear (11-12 bit usefull)

Conclusions

- There are many pure and compound semiconductors that can react to visible or near visible photons
- The usual digital/analog technologies are not suited for good sensor design
- The sensor's integrated environment in CMOS technology offers a lot advantages over CCD solution

Recommended literature

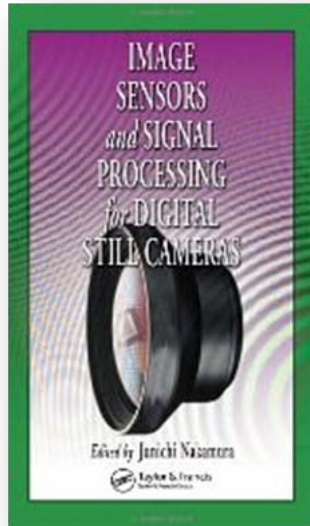


Image Sensors and Signal Processing for Digital Still Cameras

Junichi Nakamura

Publisher: CRC Press (August 5, 2005)

Comprehension questions:

- I. What is the physical phenomenon in semiconductors that enables light detection?
- II. What is difference between CCD and CMOS sensors?
- III. List some detector architectures.

